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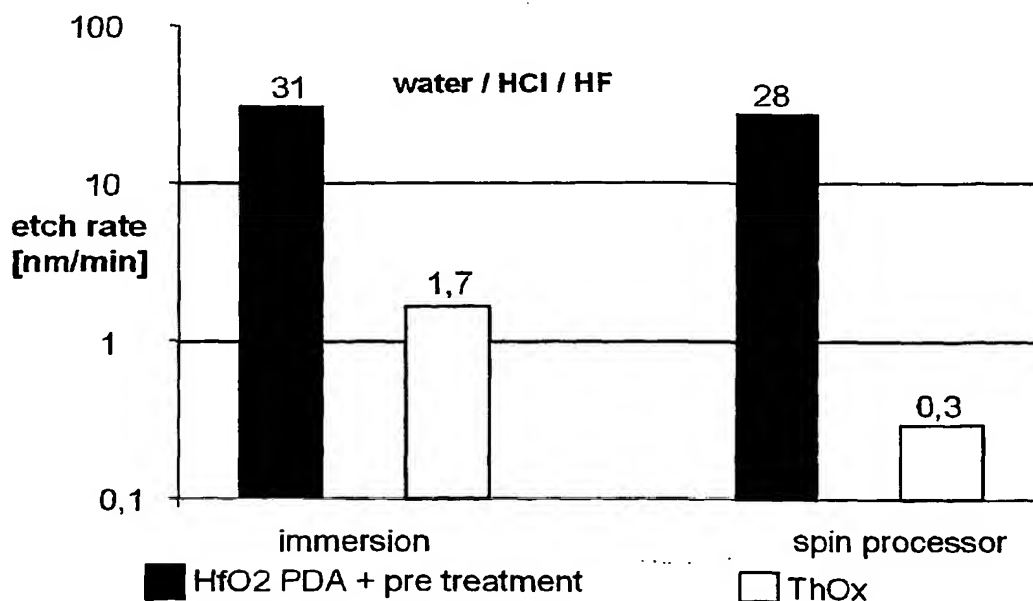
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[Continued on next page]

(54) Title: METHOD FOR SELECTIVE ETCHING



(57) Abstract: Disclosed is a method of selective etching a first material on a substrate with a high selectivity towards a second material by flowing a liquid etchant across a substrate surface at a flow sufficient fast to generate a minimum mean velocity  $v$  parallel to the substrate's surface.

WO 2005/078783 A1

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